

Benchtop Plasma System

The PE-100 is a complete plasma treatment solution – capable of plasma cleaning, plasma etching, reactive ion etching, and more.

This model is available in one of three possible configurations:

- 1) Plasma Cleaning/Plasma Etching
- 2) Reactive Ion Etching (RIE)
- 3) Convertible Configuration – Includes both isotropic and anisotropic plasma processing in a single system. Removable tray configuration.



STANDARD FEATURES

Electrode Configuration	Three Stacked Horizontal (9"W x 13"D + 3" Clearance)
Generator	300W 100KHz Continuously Variable Power Supply
Gas Control	One 0-50cc Mass Flow Controller
Control System	Laptop Equipped with Plasma Etch Inc.'s Control Software for Fully Automatic System Operation
Vacuum Gauge	1-2000 mT
Vacuum Pump	8CFM 2-Stage Direct Drive Oil Pump with Oil Mist Coalescing Filter (Oxygen Service – Krytox Charged)
Chamber	12" x 14.5" x 12"; 6061-T6 Aluminum
Unit Dimensions	17" x 28" x 30"
Unit Weight	160lbs; 228lbs with Vacuum Pump

FACILITY REQUIREMENTS

Electrical	120VAC / 60Hz @ 15A or 220VAC / 50Hz @ 14A
Compressed Air Service	80-100PSI, 0.5CFM
Regulated Process Gases	15PSI, 2-Stage Regulator

OPTIONAL FEATURES

- Custom Vacuum Chamber or Electrode Size
- Reactive Ion Electrodes
- MHz Power Supplies with Automatic Matching Network
- PC-Based Control System
- Electrostatic Shielding
- Temperature Control System
- Dry Vacuum Pump
- Chiller System for Dry Vacuum Pump
- Chamber and Vacuum Pump Purge Systems
- Vacuum Pump Oil Mist Eliminator
- Vacuum Pump Oil Filtration
- Automatic Vacuum Control
- Additional Digital Mass Flow Controllers
- Software Configurable Gas Steering Matrix 2x5
- Low Gas-Source Alarm
- Light Tower
- Fume Scrubber